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(12) **United States Design Patent** (10) **Patent No.:** **US D902,165 S**
Johanson et al. (45) **Date of Patent:** **** Nov. 17, 2020**

(54) **TARGET PROFILE FOR A PHYSICAL VAPOR DEPOSITION CHAMBER TARGET**

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(**) Term: **15 Years**

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Related U.S. Application Data

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(51) **LOC (12) Cl.** **13-03**

(52) **U.S. Cl.**

USPC **D13/182**

(58) **Field of Classification Search**

USPC D13/182; D15/144.1, 144.2, 199

CPC H01L 21/67742; H01L 21/0226; H01L 21/02263; H01L 21/02266; H01L 21/02269; H01L 21/02271; H01L 2224/75186; H01L 2224/76185; H01L 2224/76186; H01L 2221/68363

See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a target profile for a physical vapor deposition chamber target, as shown and described.

DESCRIPTION

FIG. 1 is a top perspective view of a target profile for a physical vapor deposition chamber target showing our new design;

FIG. 2 is a bottom perspective view thereof;

FIG. 3 is a top plan view thereof;

FIG. 4 is a bottom plan view thereof;

FIG. 5 is a right elevation view thereof;

FIG. 6 is a left elevation view thereof;

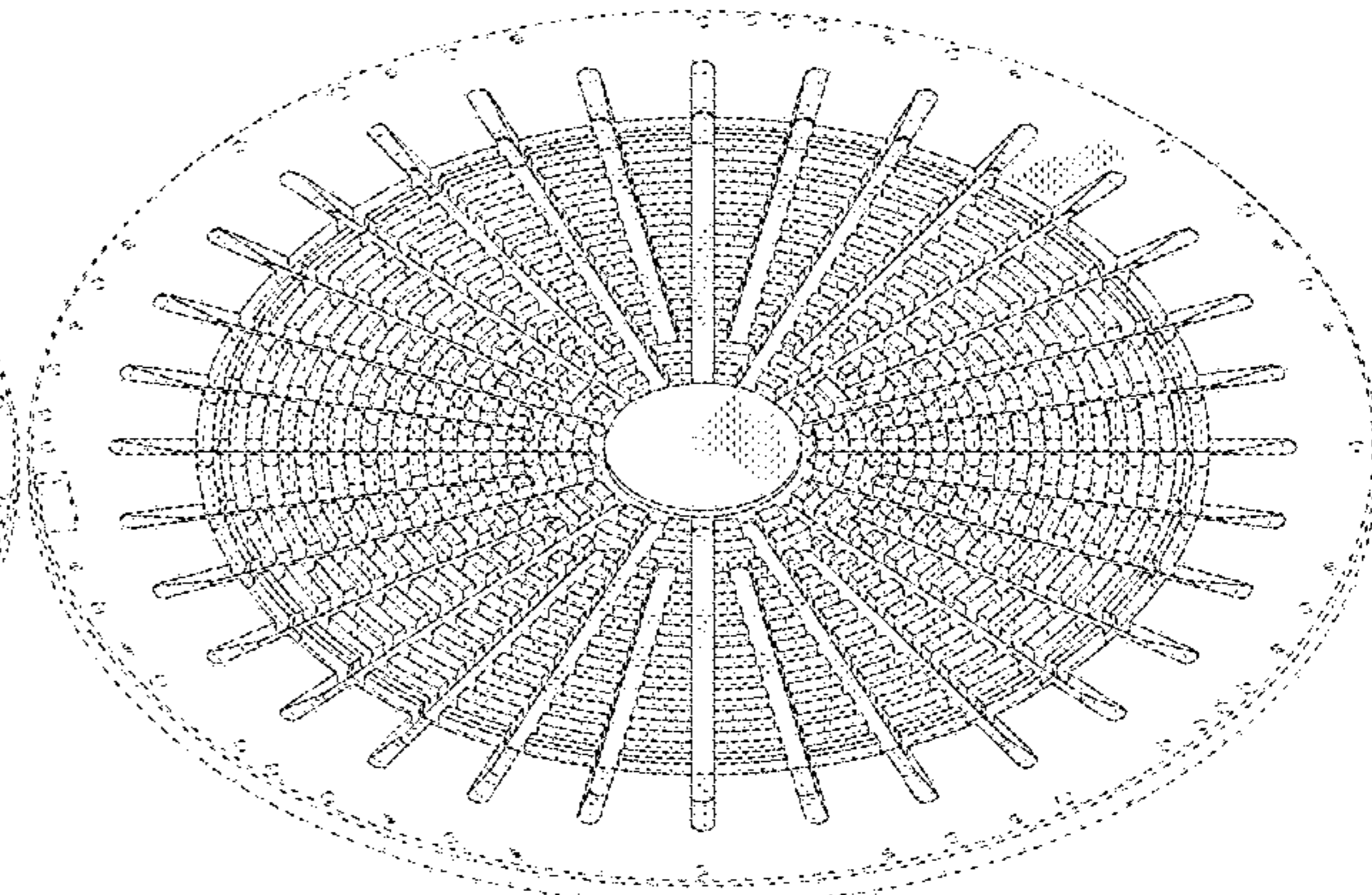
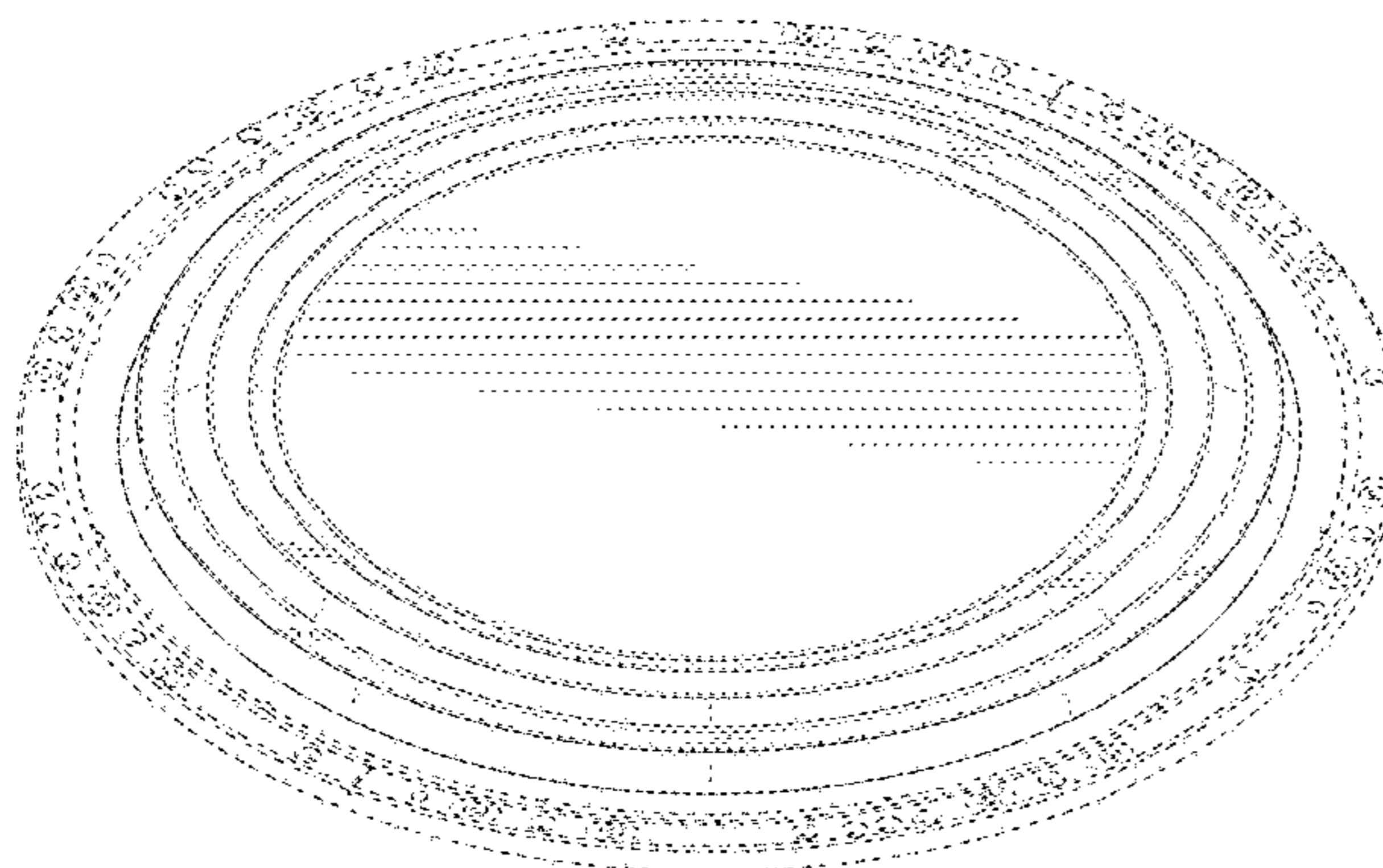
FIG. 7 is a front elevation view thereof;

FIG. 8 is a back elevation view thereof; and,

FIG. 9 is an enlarged cross sectional view taken along line 9-9 in FIG. 4.

The dashed lines in FIGS. 1-9 represent unclaimed environment and form no part of the claimed design.

1 Claim, 7 Drawing Sheets



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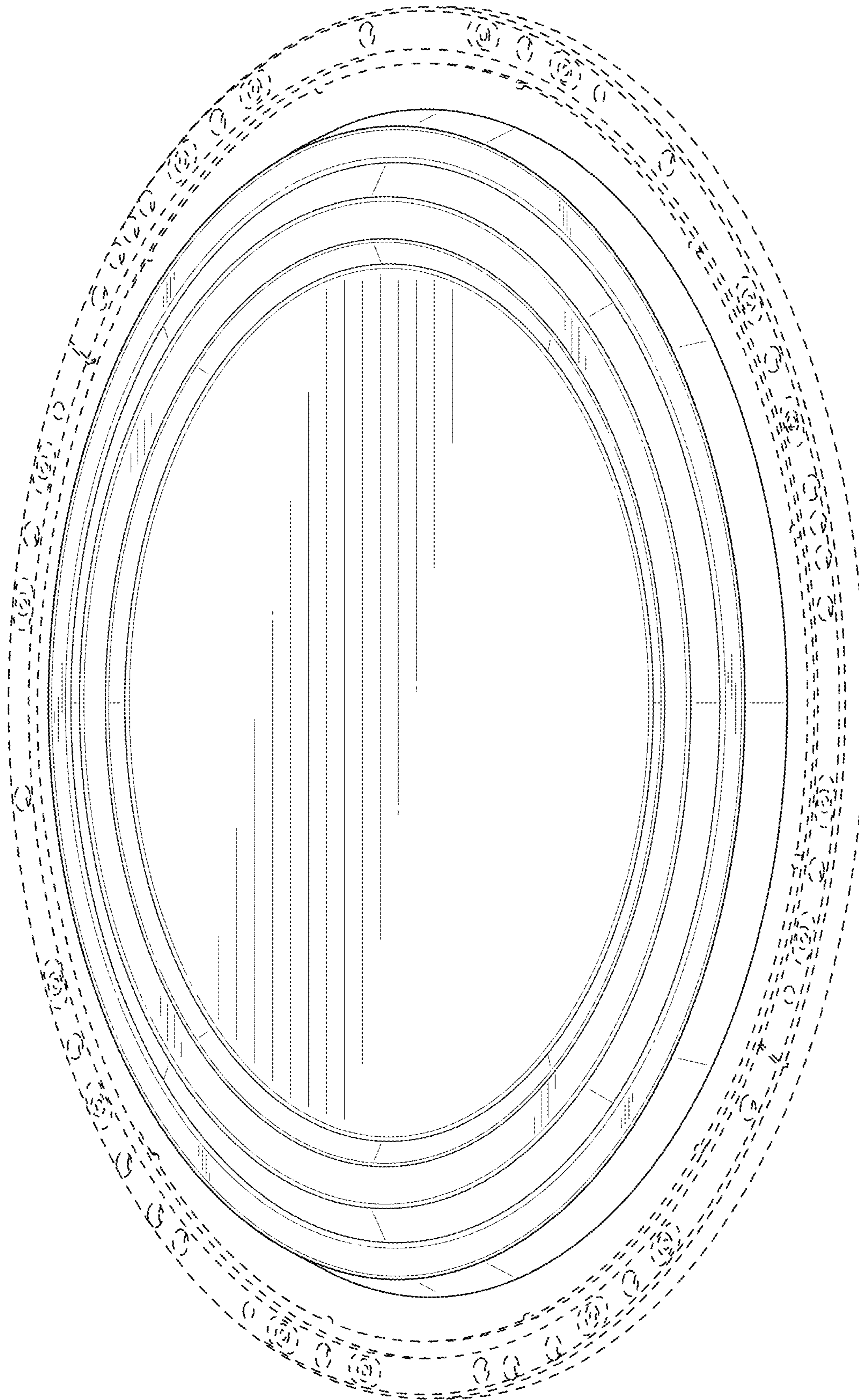


FIG. 1

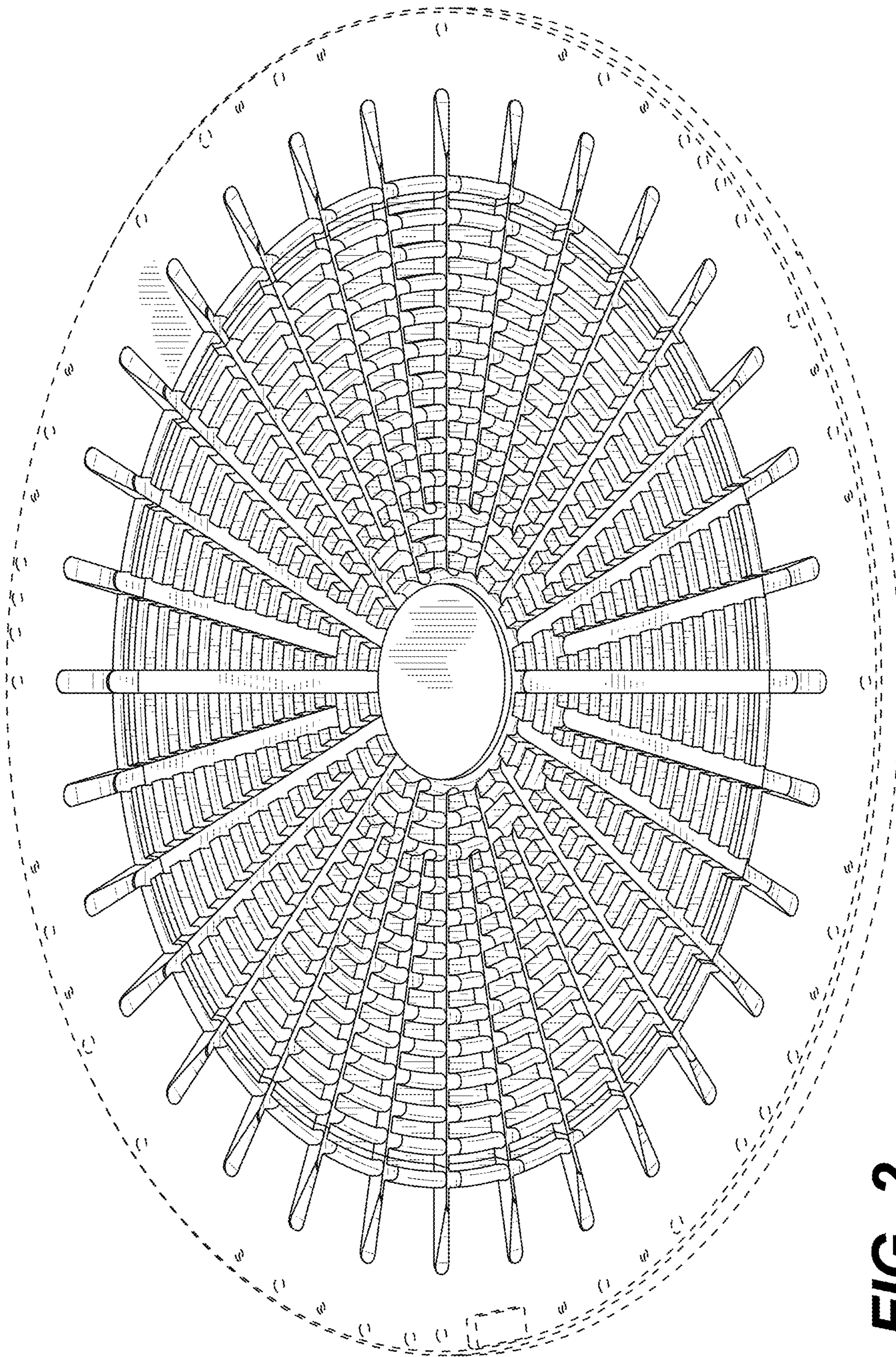


FIG. 2

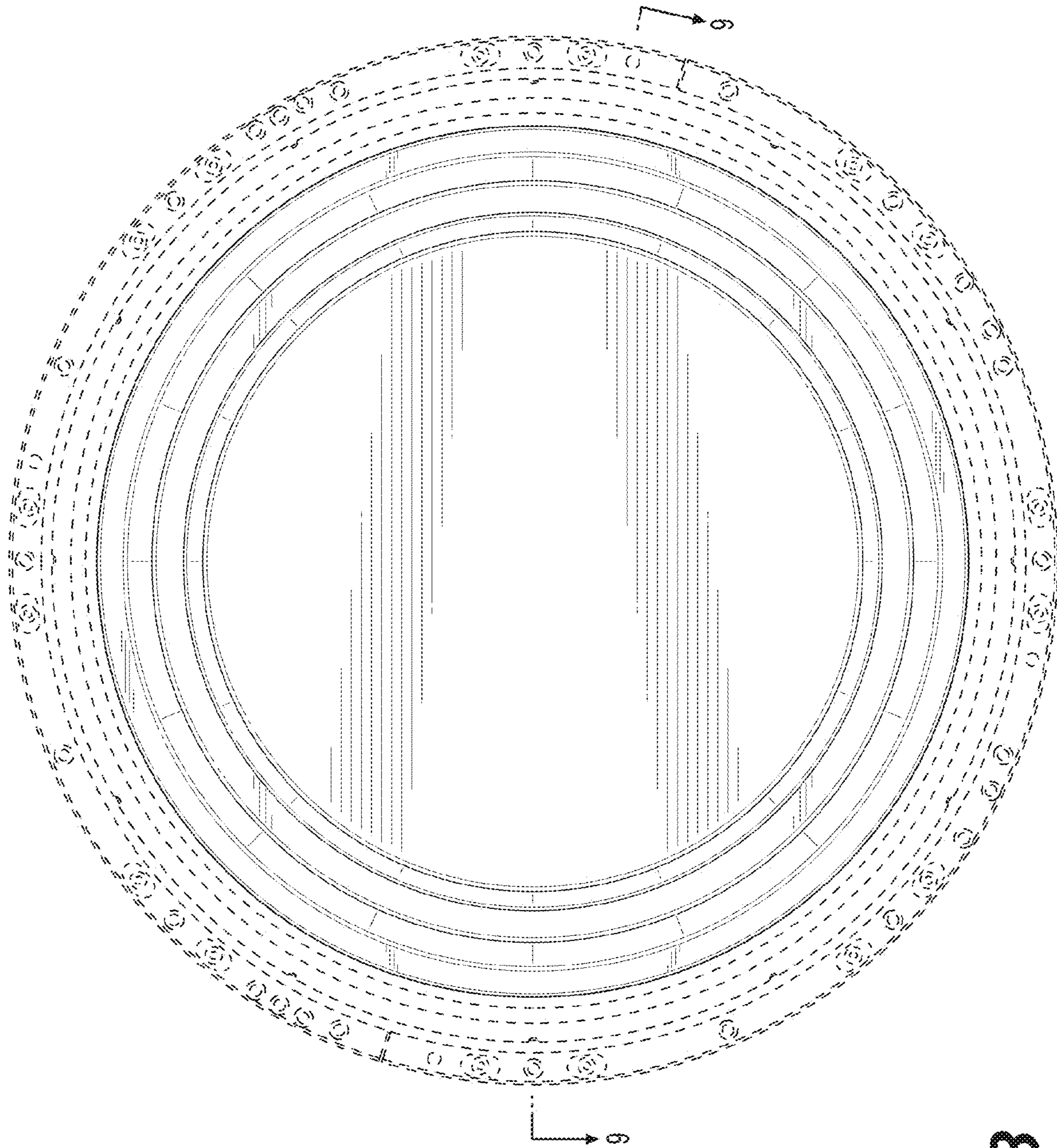


FIG. 3

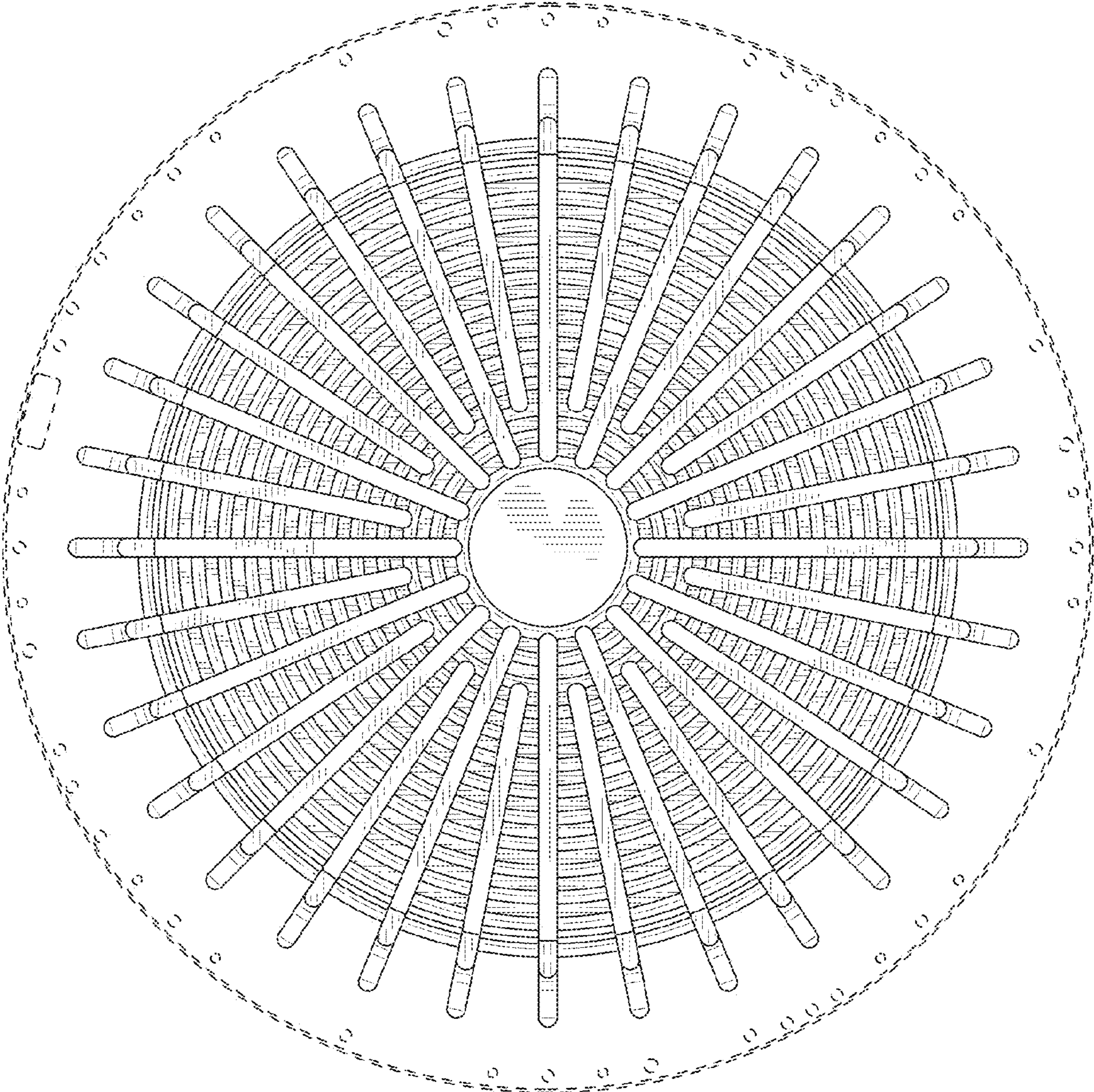


FIG. 4

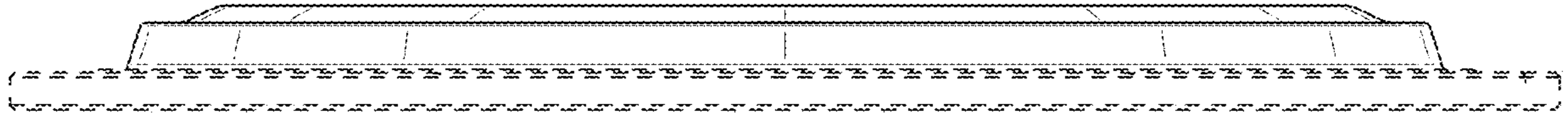


FIG. 5

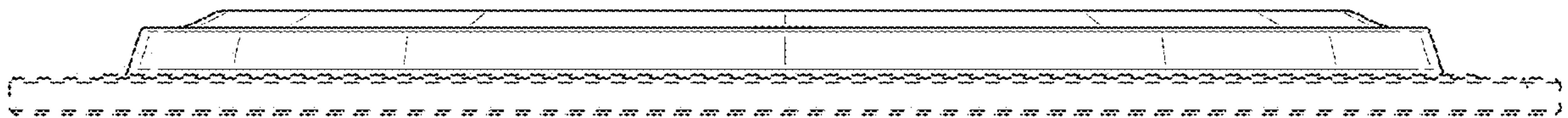


FIG. 6

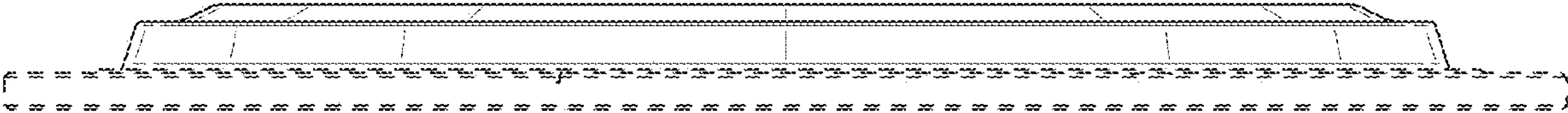


FIG. 7

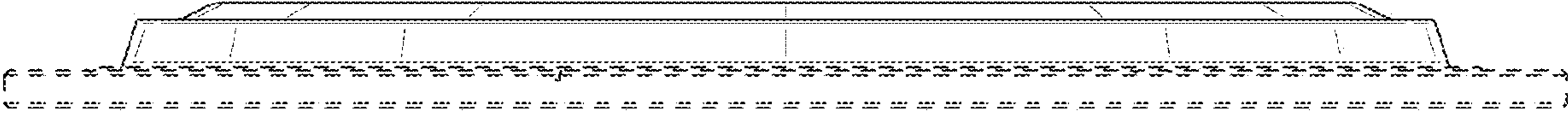


FIG. 8

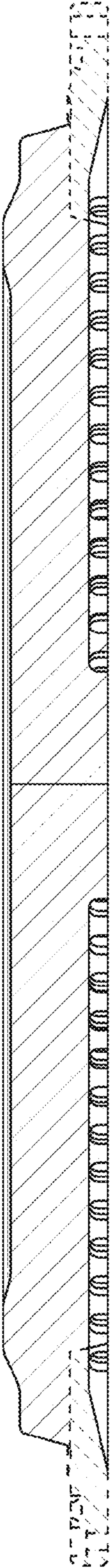


FIG. 9